
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: RAMALINGAM et al.

Attorney Docket No.:

LAM1P185/P1228

Application No.: Filed Herewith

Examiner: Unassigned


Filed: Herewith

Group: Unassigned

Title: SELECTIVE ETCH OF FILMS WITH
HIGH DIELECTRIC CONSTANT

CERTIFICATE OF EXPRESS MAILING

I hereby certify that this paper and the documents and/or fees referred to as attached therein are being deposited with the United States Postal Service on January 14, 2004 in an envelope as "Express Mail Post Office to Addressee" service under 37 CFR §1.10, Mailing Label Number ER562285862US, addressed to: Mail Stop Patent Application, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.


Sue Funchess

INFORMATION DISCLOSURE STATEMENT
37 CFR §§1.56 AND 1.97(b)

Mail Stop Patent Application
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure

Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 50-0388 (Order No. LAM1P185).

Respectfully submitted,

BEYER WEAVER & THOMAS, LLP

A handwritten signature in black ink, appearing to read "Michael Lee", with a stylized, flowing script.

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Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. LAM1P185/P1228	Application No.: Filed Herewith
	Applicant: RAMALINGAM et al.	Group Unassigned
	Filing Date Herewith	

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A	3,398,033	08/20/68	Haga et al.	156	17	02/26/65
	B	4,351,894	09/28/82	Yonezawa et al.	430	313	05/12/81
	C	4,595,453	06/17/86	Yamazaki et al.	156	643	09/24/84
	D	4,865,685	09/12/89	Palmour	156	643	11/03/87
	E	4,981,551	01/01/91	Palmour	156	643	09/06/89
	F	6,090,304	07/18/00	Zhu et al.	216	79	08/28/97
	G	6,432,779B1	08/13/02	Hobbs et al.	438	287	01/30/01
	H	6,451,647B1	09/17/02	Yang et al.	438	240	03/18/02
	I	6,511,872B1	01/28/03	Donnelly, Jr. et al.	438	197	07/10/01
	J	20030000546	01/02/03	Richardson et al.	134	1.1	05/03/02
	K	20030170986	09/11/03	Nallan et al.	438	689	03/06/02

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	L							
	M							
	N							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	O	Pelhos et al., "Etching of High-K Dielectric $Zr_{1-x}Al_xO_y$ Films in Chlorine-Containing Plasmas", J. Vac. Sci. Technol. A 19(4), Jul/Aug 2001, pages 1361-1366
	P	Sha et al., "Plasma Etching Selectivity of ZrO_2 to Si in BCl_3/Cl_2 Plasmas", J. Vac. Sci. Technol. A 21(6), Nov/Dec 2003, pages 1915-1922
	Q	
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.